

ABSTRACT OF THE DISCLOSURE

A method and a measuring instrument for determining the position of an edge to be measured on a pattern on a substrate are described. A complete, nonlinear model intensity profile, which identifies the edge to be measured, of a model edge is ascertained and stored, and a desired edge position x_k is defined therein with subpixel accuracy. A camera image of the substrate having the edge to be measured is acquired, and a one-dimensional measured intensity profile of the edge to be measured is determined therefrom. The model intensity profile is identified in the measured intensity profile with an indication of its location x_m relative to a reference point. The desired position p of the edge to be measured is determined with subpixel accuracy as $p = x_m + x_k$.

(FIG. 8)